

ABSTRACT OF THE DISCLOSURE

A positive resist composition comprising:

(A) a fluorine group-containing resin having: a structure wherein at least one of the main chain and the side chain of the polymer skeleton has at least one fluorine atom; and having a group capable of decomposing under the action of an acid to increase the solubility in an alkali developer;

(B) a compound capable of generating an acid upon irradiation with one of actinic ray and radiation, and

(C) a surfactant containing at least one of a silicon atom and a fluorine atom.